L Number	Hits	Search Text	DB	Time stamp
34	5	("5189812" | "5325604" | "5458687" | "5609720" | "5791895").PN.	USPAT	2003/07/29 10:50
64	15	("4469529" | "5108792" | "5345534" | "5551985" | "5595606" | "5624499" | "5650082" | "5683518" | "5708755" | "5711815" | "5846476" | "5889258" | "5900177" | "5937142" | "5970214").PN.	USPAT	2003/07/29 12:04
65	106249	(adjust$4 control$4 var$4 increas$3 decreas$3 lower$3 rais$3) near5 temperature near12 (antifreeze anti-freeze glycol ethyleneglycol water refrigerant ((((heat near2 transfer$4 near2 (fluid medium liquid gas vapor)) (heat near2 exchang$3 near2 (fluid medium liquid gas vapor))) (coolant or (cooling near2 (fluid medium liquid gas vapor)))) (thermal near2 transfer$4 near2 (fluid medium liquid gas vapor)) (thermal near2 exchang$3 near2 (fluid medium liquid gas vapor))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/29 12:09
66	26170	(adjust$4 control$4 var$4 increas$3 decreas$3 lower$3 rais$3) near12 (((flow$3 circulat$3 suppl$4) near3 (rate speed)) near8 (antifreeze anti-freeze glycol ethyleneglycol water refrigerant ((((heat near2 transfer$4 near2 (fluid medium liquid gas vapor)) (heat near2 exchang$3 near2 (fluid medium liquid gas vapor))) (coolant or (cooling near2 (fluid medium liquid gas vapor)))) (thermal near2 transfer$4 near2 (fluid medium liquid gas vapor)) (thermal near2 exchang$3 near2 (fluid medium liquid gas vapor)))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/29 12:10
67	611	(adjust$4 control$4 var$4 increas$3 decreas$3 lower$3 rais$3) near5 (power energy) near10 (process lamp ion electron) near10 (temperature near3 (wafer substrate workpiece plate susceptor pedestal support table chuck holder))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/29 17:00
69	18	((adjust$4 control$4 var$4 increas$3 decreas$3 lower$3 rais$3) near12 (((flow$3 circulat$3 suppl$4) near3 (rate speed)) near8 (antifreeze anti-freeze glycol ethyleneglycol water refrigerant ((((heat near2 transfer$4 near2 (fluid medium liquid gas vapor)) (heat near2 exchang$3 near2 (fluid medium liquid gas vapor))) (coolant or (cooling near2 (fluid medium liquid gas vapor)))) (thermal near2 transfer$4 near2 (fluid medium liquid gas vapor)) (thermal near2 exchang$3 near2 (fluid medium liquid gas vapor)))))) and ((adjust$4 control$4 var$4 increas$3 decreas$3 lower$3 rais$3) near5 (power energy) near10 (process lamp ion electron) near10 (temperature near3 (wafer substrate workpiece plate susceptor pedestal support table chuck holder)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/29 12:14
70	41	5200023.URPN.	USPAT	2003/07/29 12:16
71	9	("3664942" | "3718757" | "4396478" | "4675072" | "4883560" | "4913790" | "4919542" | "4936967" | "4971653").PN.	USPAT	2003/07/29 12:46
72	11	4396478.URPN.	USPAT	2003/07/29 12:55
73	18	("4184480" | "4409511" | "4427378" | "4680447" | "4920918" | "4945251" | "5145716" | "5152060" | "5743643" | "5762713" | "5781693" | "5790751" | "5863334" | "5960158" | "6143079" | "6148761" | "6284051" | "6435869").PN.	USPAT	2003/07/29 13:15
68	68	((adjust$4 control$4 var$4 increas$3 decreas$3 lower$3 rais$3) near5 temperature near12 (antifreeze anti-freeze glycol ethyleneglycol water refrigerant ((((heat near2 transfer$4 near2 (fluid medium liquid gas vapor)) (heat near2 exchang$3 near2 (fluid medium liquid gas vapor))) (coolant or (cooling near2 (fluid medium liquid gas vapor)))) (thermal near2 transfer$4 near2 (fluid medium liquid gas vapor)) (thermal near2 exchang$3 near2 (fluid medium liquid gas vapor))))) and ((adjust$4 control$4 var$4 increas$3 decreas$3 lower$3 rais$3) near5 (power energy) near10 (process lamp ion electron) near10 (temperature near3 (wafer substrate workpiece plate susceptor pedestal support table chuck holder)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/29 14:42

C:\APPS\east\workspaces\09-670975.wsp

74	55	(((adjust$4 control$4 var$4 increas$3 decreas$3 lower$3 rais$3) near5 temperature near12 (antifreeze anti-freeze glycol ethyleneglycol water refrigerant ((((heat near2 transfer$4 near2 (fluid medium liquid gas vapor)) (heat near2 exchang$3 near2 (fluid medium liquid gas vapor))) (coolant or (cooling near2 (fluid medium liquid gas vapor)))) (thermal near2 transfer$4 near2 (fluid medium liquid gas vapor)) (thermal near2 exchang$3 near2 (fluid medium liquid gas vapor))))) and ((adjust$4 control$4 var$4 increas$3 decreas$3 lower$3 rais$3) near5 (power energy) near10 (process lamp ion electron) near10 (temperature near3 (wafer substrate workpiece plate susceptor pedestal support table chuck holder)))) not (((adjust$4 control$4 var$4 increas$3 decreas$3 lower$3 rais$3) near12 (((flow$3 circulat$3 suppl$4) near3 (rate speed)) near8 (antifreeze anti-freeze glycol ethyleneglycol water refrigerant ((((heat near2 transfer$4 near2 (fluid medium liquid gas vapor)) (heat near2 exchang$3 near2 (fluid medium liquid gas vapor))) (coolant or (cooling near2 (fluid medium liquid gas vapor)))) (thermal near2 transfer$4 near2 (fluid medium liquid gas vapor)) (thermal near2 exchang$3 near2 (fluid medium liquid gas vapor))))) and ((adjust$4 control$4 var$4 increas$3 decreas$3 lower$3 rais$3) near5 (power energy) near10 (process lamp ion electron) near10 (temperature near3 (wafer substrate workpiece plate susceptor pedestal support table chuck holder))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/29 16:58
75	13	5605600.URPN.	USPAT	2003/07/29 16:27
76	13	5605600.URPN.	USPAT	2003/07/29 16:27
77	19	("4261762" | "4457359" | "4508161" | "4533430" | "4855017" | "4903754" | "4949783" | "4963713" | "5001423" | "5093579" | "5155331" | "5191218" | "5203958" | "5267607" | "5270266" | "5290381" | "5320982" | "5366002" | "5458734").PN.	USPAT	2003/07/29 16:27
78	1582	((control$4 adjust$4) near3 temperature near10 (wafer substrate workpiece plate susceptor pedestal support table chuck holder)).ti.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/29 17:00
79	1017	(((control$4 adjust$4) near3 temperature near10 (wafer substrate workpiece plate susceptor pedestal support table chuck holder)).ti.) and (VLSI ULSI semiconductor wafer substrate (integrated adj circuit))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/29 17:21
80	18	((adjust$4 control$4 var$4 increas$3 decreas$3 lower$3 rais$3) near5 (power energy) near10 (process lamp ion electron) near10 (temperature near3 (wafer substrate workpiece plate susceptor pedestal support table chuck holder))) and ((((control$4 adjust$4) near3 temperature near10 (wafer substrate workpiece plate susceptor pedestal support table chuck holder)).ti.) and (VLSI ULSI semiconductor wafer substrate (integrated adj circuit)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/29 17:21

C:\APPS\east\workspaces\09-670975.wsp